

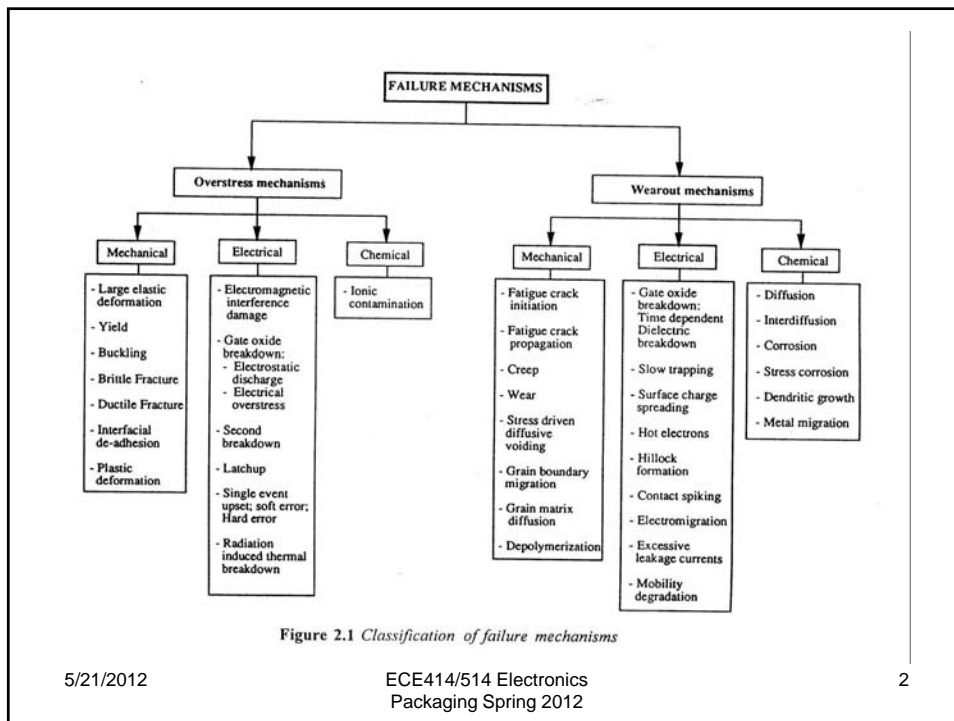
# ECE414/514

## Electronics Packaging

### Fall 2012 Lecture 15

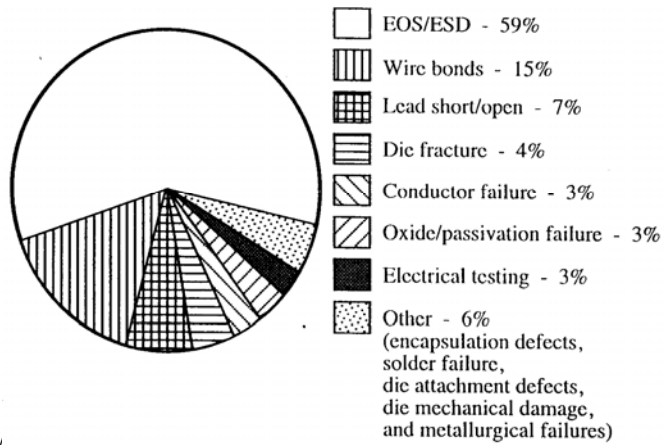
## Reliability Failure Mechanisms: fracture mechanics, fatigue, electromigration & popcorning

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Dept of Electrical & Computer Engineering  
Portland State University



## Distribution of Failures: Commercial integrated circuits (PEMs)

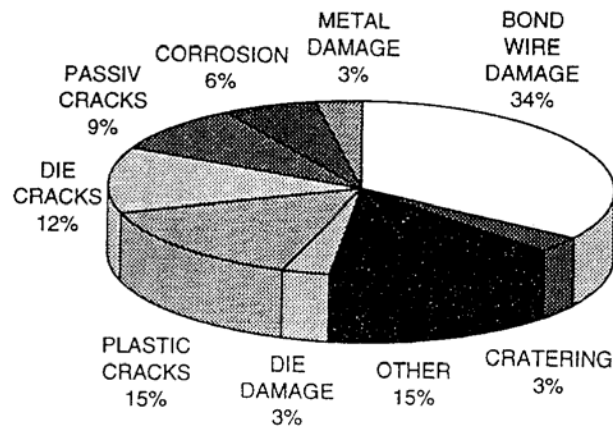
FAILURE MECHANISMS, SITES, AND MODES



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## Temperature Cycle Failures

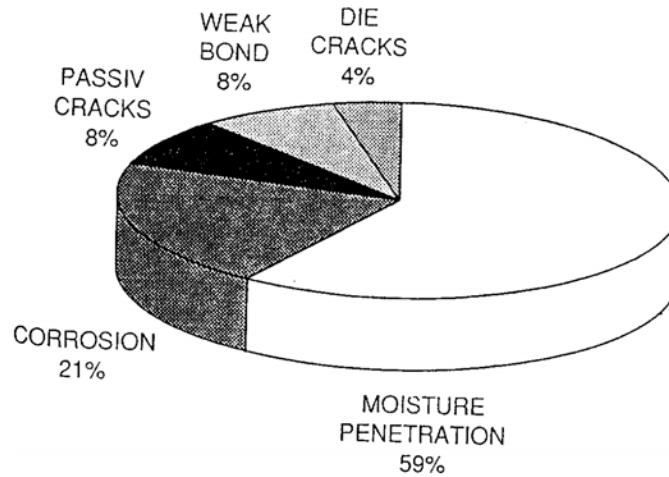


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# HAST Failures: 1988-1994



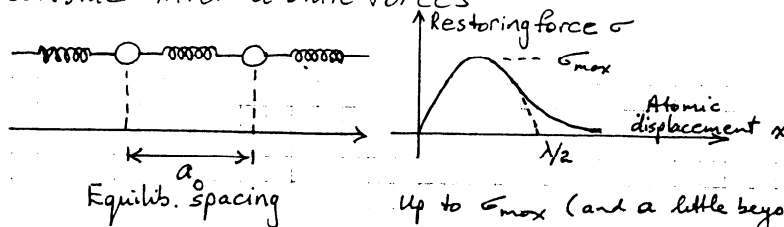
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## Ideal/Theoretical Fracture Strength

Consider inter-atomic forces



approximate by  $\sigma = \sigma_{max} \sin\left(\frac{2\pi x}{\lambda}\right)$

For small increments  $x$ :

$$\text{Crystal strain} = \frac{dx}{a_0}$$

& in the elastic region  $E = \frac{\text{stress}}{\text{strain}} = \frac{d\sigma}{dx/a_0}$   
(Young's modulus)

$$\therefore \frac{d\sigma}{dx} = \frac{E}{a_0} = \sigma_{max} \cos\left(\frac{2\pi x}{\lambda}\right) \times \frac{2\pi}{\lambda} \approx \frac{2\pi}{\lambda} \sigma_{max} \quad (\text{for } x \ll \lambda)$$

$$\therefore \sigma_{max} = \frac{\lambda E}{2\pi a_0} \approx \frac{E}{2\pi} \quad \text{if } \lambda \sim a_0$$

$\sigma_{max}$  corresponds to the point where the interatomic forces would yield, i.e. the material should break at about  $\sigma_{max} = E/10$

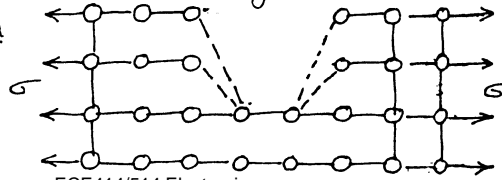
In practice:  $\sigma_f$  (measured)  $\sim E/10^4$

(But very small samples i.e. thin films or whiskers can reach  $\sigma_f \sim E/15$  or so.)

POSTULATE: Small flaws or micro-cracks.

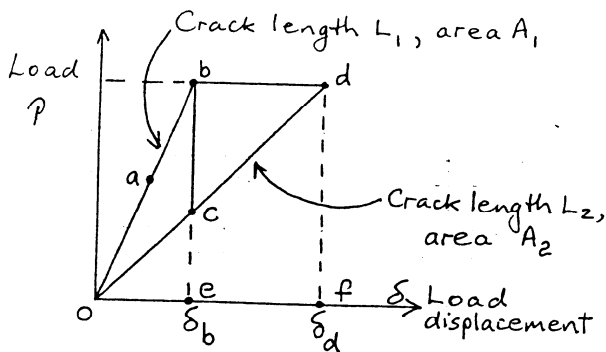
(Statistically less likely to occur in a very small sample, hence size effect.)  $\rightarrow$  Thin fibers stronger than thick rods.)

Stress concentration

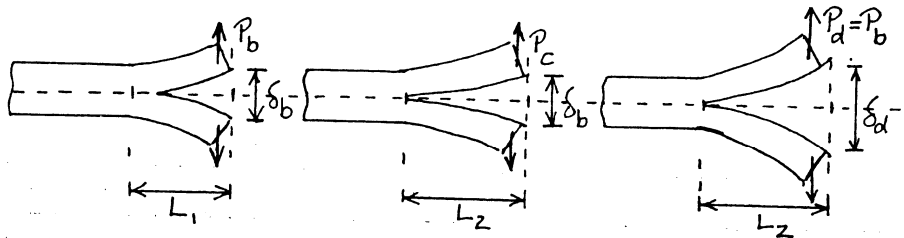


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## Crack Mechanics



(Perpendicular sample thickness is  $t$ ;  
 $\therefore A_1 = tL_1$   
 $A_2 = tL_2$ )



Ob — elastic relationship for small crack  $L_1$

Od — " " " " large "  $L_2$

When crack grows  $L_1 \rightarrow L_2$ , elastic curve shifts  $b \rightarrow d$   
 if crack propagation  $L_1 \rightarrow L_2$  at constant displacement  $S_b$   
 (or  $b \rightarrow d$  if at constant load  $P_b = P_d$ )

Work is done to open crack:

For constant displacement  
 $b \rightarrow c$   
 Initial stored energy at  $b$  = Area Obe  
 Final stored energy  $\Rightarrow$  Area Oce  
 $\therefore$  Work to open crack  $\Rightarrow$  Area (Obe - Oce) = Area Obc  
 Supplied from internal stored energy.  
 Reduced stored energy - - -

For constant load  
 $b \rightarrow d$   
 $P S_b = \text{area Obe}$   
 Area Odf = Oce from storage + ecdf from work.  
 Area (Obe + bdfc - Odf) = Obd  
 Represents external work  $P_e$  distance = Obc from internal storage + bdc from external work.

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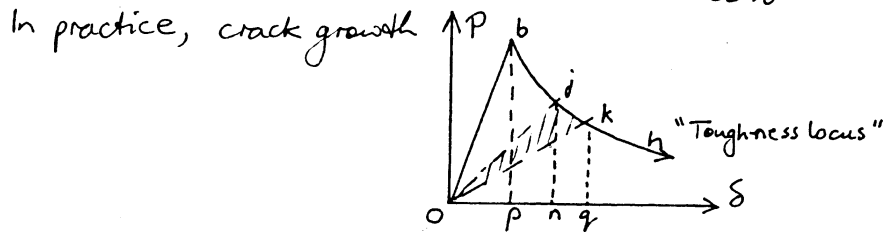
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Energy absorbed by growth  
 i.e. Work =  $R(A_2 - A_1)$  where  $R$  = fracture toughness  
 =  $R(L_2 - L_1)$

$\therefore R \Rightarrow \frac{\text{Area Obc}}{A_2 - A_1} \quad \frac{\text{Area Obd}}{A_2 - A_1}$   
 (greater, representing external work done)

For incremental crack growth  $L_2 = L_1 + \Delta L$   
 & for large  $P$ , the difference (Area bdc)  $\rightarrow 0$   
 $bd \rightarrow 0$   
 $bc \rightarrow 0$



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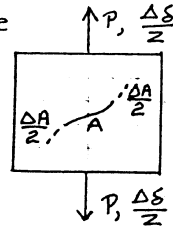
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ENERGY BALANCE for general case

External work =  $P \Delta \delta$

Crack growth absorbs energy =  $R \Delta A$

Strain energy  $\Delta$  changes by  $\Delta \Lambda$



Strain energy at j is area  $Ojn = 1/2 PS$

$\therefore \Delta \Lambda = 1/2 \Delta (PS)$

$\therefore$  External work  $P \Delta \delta = \Delta \Lambda$  +  $R \Delta A$   
Change in internal strain energy      Crack growth takes energy.

$P \Delta \delta = 1/2 \Delta (PS) + R \Delta A$   
 $= 1/2 P \Delta \delta + 1/2 \delta \Delta P + R \Delta A$

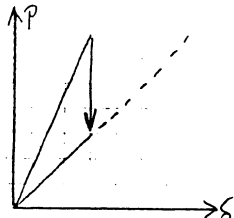
ie.  $P \Delta \delta - \delta \Delta P = 2R \Delta A$

$\frac{1}{P} \frac{\Delta \delta}{\Delta A} - \frac{\delta}{P^2} \frac{\Delta P}{\Delta A} = \frac{2R}{P^2}$  &  $\frac{P}{\delta} = \text{"stiffness"}$

$\frac{d}{dA} \left( \frac{\delta}{P} \right) = \frac{2R}{P^2} \rightarrow P_{crack}^2 = \frac{2R}{dA \left( \frac{\delta}{P} \right)}$  11

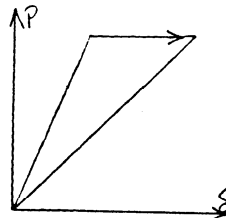
Note on notation: Using  $R$  fracture toughness here. 4.24

Commonly  $R$  written  $G_c$  "critical strain energy release rate"



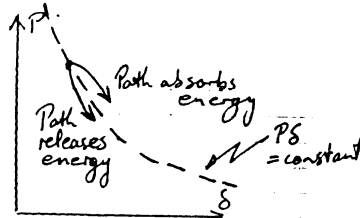
Constant displacement

Final energy < Initial  
 $\therefore$  "released" by crack propagation



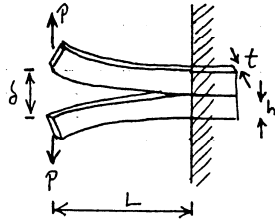
Constant Load

Final energy > Initial  
 ie. ~~absorbed~~ absorbed by crack propagation



$\therefore$  energy "release" not general

Case 1: Thin beam



For cantilever beam, deflection  $\frac{\delta}{2} = \frac{PL^3}{3EI}$

where  $I = th^3/12$

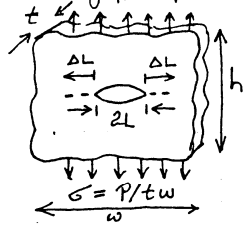
so  $\frac{\delta}{P} = \frac{2}{3} \frac{L^3}{EI}$

&  $dA = t dL$

so  $\frac{d(\delta/P)}{dA} = \frac{1}{t} \frac{d}{dL} \left( \frac{2}{3} \frac{L^3}{EI} \right) = \frac{2L^2}{EI t}$

$P_{crack}^2 = REI t / L^2$

Case 2: "Griffith" problem: elliptical crack



Stiffness  $P/\delta = \frac{Etw}{h(1 + 2\pi \frac{L^2}{hw})}$  ← Young's modulus of "flawless" material

&  $A = 2Lt \therefore dA = 2t \cdot dL$

&  $\frac{d(\delta/P)}{dA} = \frac{1}{2t} \frac{h4\pi L/hw}{Etw} = 2\pi \frac{L}{E t^2 w^2}$

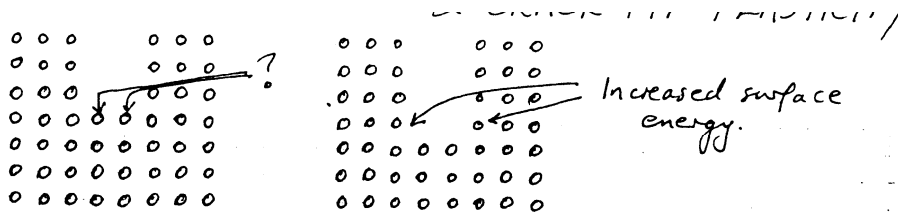
$\therefore P_{crack}^2 = \frac{2R}{2\pi L/Et^2 w^2} = \frac{ER}{\pi L} \cdot (tw)^2$

&  $\sigma_{crack}^2 = ER/\pi L$

This is the Griffith equation for brittle fracture

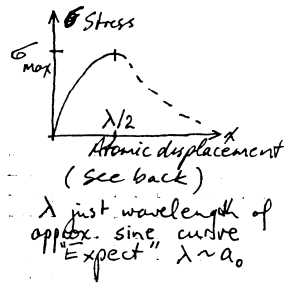
Implies critical crack length, below which crack will NOT run for given stress.

## Physical Process: Microscopic Interpretation & Crack Tip Plasticity



Energy supplied to crack propagation

→ increase in surface energy (broken bonds require energy input)



∴ Work done to fracture

$$= \int_0^{\lambda/2} \sigma_{max} \sin\left(\frac{2\pi x}{\lambda}\right) dx$$

$$= \left[-\cos\left(\frac{2\pi x}{\lambda}\right)\right]_0^{\lambda/2} \sigma_{max} \frac{\lambda}{2\pi}$$

$$= \lambda \sigma_{max} / \pi$$

= Increase in energy of TWO surfaces

$$= 2\gamma_s \leftarrow \text{surface energy}$$

i.e.  $\sigma_{max} = \frac{2\pi}{\lambda} \gamma_s$  relates  $\sigma_{max}$  to  $\gamma_s$

Compare previously (without  $\lambda \sim a_0$  approx):  $\sigma_{max} = \frac{\lambda}{2\pi a_0} F$  relates  $\sigma_{max}$  to  $F$

Suggests  $F = \left(\frac{2\pi}{\lambda}\right)^2 a_0 \gamma_s$  (or  $\sigma_{max} = E/2\pi$  if  $\lambda = a_0$ )

Another commonly quoted result from ~~the~~

$$\sigma_{max} = \frac{2\pi \gamma_s}{\lambda} \text{ \& } \sigma_{max} = \frac{\lambda E}{2\pi a_0} \rightarrow \sigma_{max} = \sqrt{\frac{E \gamma_s}{a_0}} \rightarrow \sqrt{\frac{E R}{\pi L}}$$

if  $R = 2\gamma_s$   
&  $L = 2a_0/\pi$

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Note: These variations all seem to be about the same as the first theoretical attempt

i.e.  $\sigma_{max} \sim E/10$

which we already know is OK for very small (no crack) specimens, but too high for general use.

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(a) Consider brittle materials (eg glass):

By measurement  $R \sim \gamma_s$

So use the implied  $R = 2\gamma_s$  above

$$\text{\& } \sigma_{crack} = \sqrt{\frac{E R}{\pi L}} \rightarrow \sqrt{\frac{2E\gamma_s}{\pi L}} \approx \sqrt{\frac{E\gamma_s}{L}}$$

*Griphth's equation for brittle materials*

(b) Consider ductile materials:  $R \gg \gamma_s$   
(typ  $R \approx 1000\gamma_s$ )

Extra work goes into plastic deformation of crack tip zone



## Brittle Cracking in Large/Practical Structures

There WILL be flaws! So fracture based on the existence of an initiating crack &  $\sigma^2 \propto ER/L$

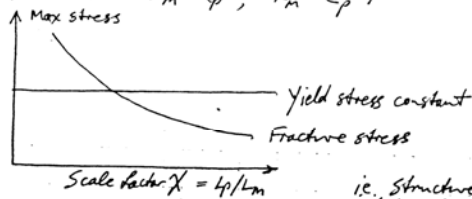
Consider large prototype structure & laboratory test model dimensions  $L_p = X L_m$ ,  $L_m$

$$\therefore \sigma_p^2 \propto E_p R_p / L_p \quad \& \quad \sigma_m^2 \propto E_m R_m / L_m$$

$$\& \quad \sigma_p^2 = (L_m / L_p) \sigma_m^2$$

$$\sigma_p = X^{-1/2} \sigma_m \quad (X > 1)$$

(assumes  $R_m = R_p$ ,  $E_m = E_p$ )



i.e. structure which yields in laboratory model, may fracture in full scale.

i.e. ductile material in lab may fail by fracture in large specimens

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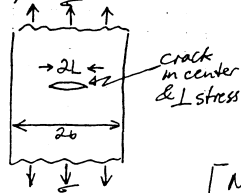
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## Fracture Mechanics

The ACTUAL fracture point is controlled by the stress field detail around the tip of the flaw/crack.

Define ① STRESS INTENSITY FACTOR =  $K$

e.g.



$$K = \sigma \sqrt{\pi L} \cdot \sqrt{\frac{2b}{\pi L} \tan^{-1}(\pi L / 2b)} \rightarrow \sigma \sqrt{\pi L}$$

Small L/b

& define ②  $K_c = \sqrt{ER}$   
= CRITICAL STRESS INTENSITY FACTOR

[ Note also ③ STRESS CONCENTRATION FACTOR  
(dimensionless) =  $\frac{\text{local average stress at cross section change}}{\text{average stress}}$  ]

For small  $L/b$ , cracking occurs when  $K \geq K_c$

$$\sigma \sqrt{\pi L} \geq \sqrt{ER}$$

for limiting case of small  $L/b$  i.e. when  $\sigma \sqrt{\frac{ER}{\pi L}}$

In general, cracking/fracture occurs when

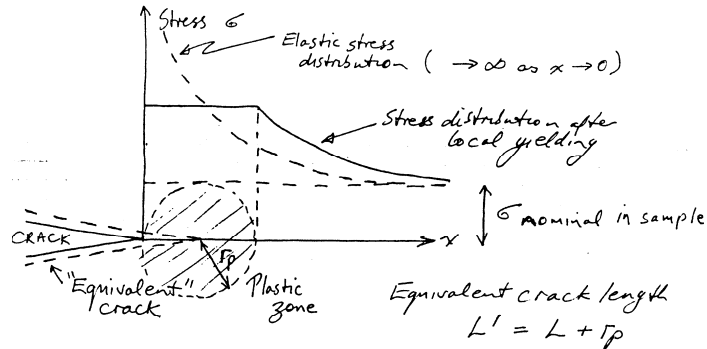
$$K = \sigma \sqrt{\pi L} \cdot Y \geq K_c = \sqrt{ER}$$

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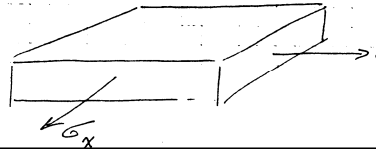
Y function of: (1) body shape/geometry (2) crack orientation & (3) type of loading

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# Plastic Zone Correction



where  $r_p = \frac{1}{2\pi} \left(\frac{K}{\sigma_y}\right)^2$  for "plane stress" case  
 or  $r_p = \frac{1}{3} \cdot \frac{1}{2\pi} \left(\frac{K}{\sigma_y}\right)^2$  for "plane strain" case  
 (typically plate of thickness  $\geq 2r_p$  so  $\sim 0$  strain in 3 direction.)



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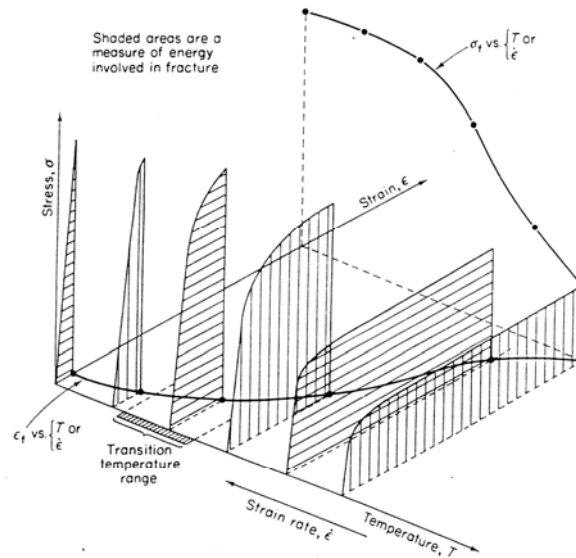


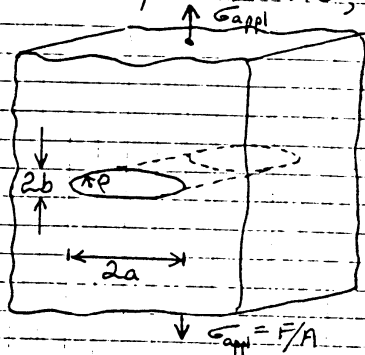
Figure 14-4 Relations between stress, strain, strain rate, and temperature in fracture. Brittle stress-strain curves transform to ductile curves at increasing temperature or decreasing strain rate (and vice versa) for most materials. Shaded areas under  $\sigma-\epsilon$  curves are some measure of the energy involved in fracture. Change from brittle to ductile behavior takes place over a reasonably narrow span of temperature, called the transition temperature range; the position of this temperature range can vary with type of test piece and conditions of measurement.

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# Stress Concentration

Basic Case: elliptical hole, stress  $\perp$  major axis



At end of major axis

$$\frac{\sigma_{max}}{\sigma_{appl}} = 1 + \frac{2a}{b}$$

$$\rho = \frac{b^2}{a} \rightarrow 1 + 2\sqrt{a/\rho}$$

radius of curvature at end of ellipse

$$\& \text{for } a \gg \rho \rightarrow 2\sqrt{a/\rho}$$

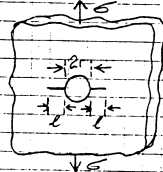
Hence stress concentration factor  $K_t \approx \frac{\sigma_{max}}{\sigma_{appl}} \approx 2\sqrt{a/\rho}$

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# Crack Initiation & Growth



For hole & crack

(a) If  $l \ll r$  (long crack solution)

Stress intensity factor  $K_I \approx \sigma \sqrt{\pi a}$

where  $a = r + l$  (as for static cracks)

(b) If  $l \gg r$

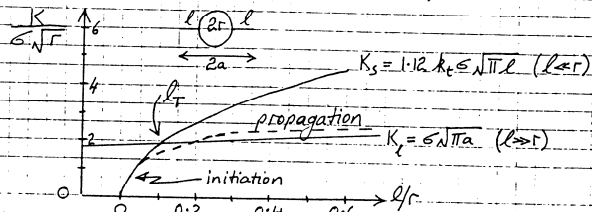
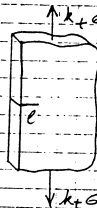
(limiting case is edge crack  $\rightarrow$ )

& stress intensity factor  $K_I = 1.12 K_t \sigma \sqrt{\pi l}$

Surface Flaw Correction Factor

Stress concentration factor for hole in infinite plate

(short crack solution)

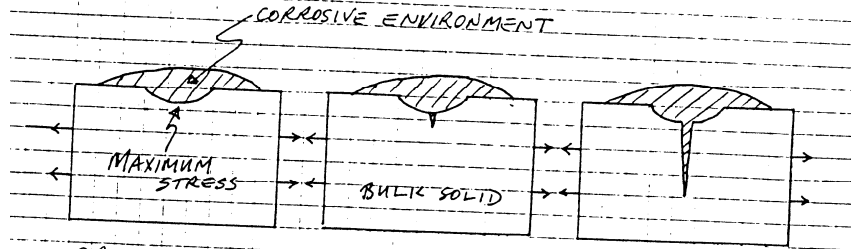


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Use  $l_r$  as the definition of crack initiation.

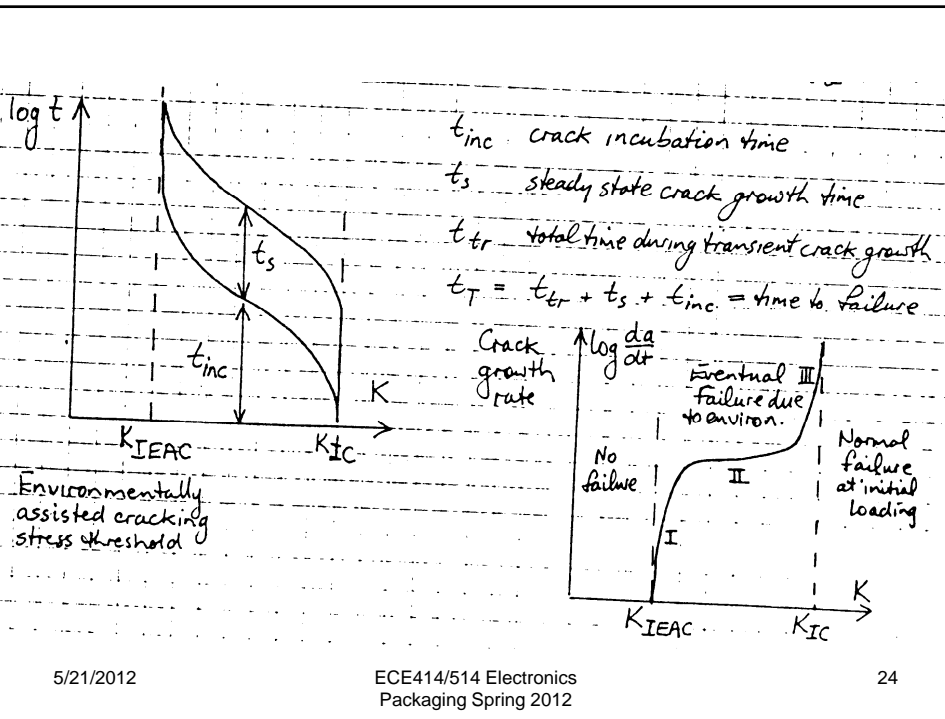
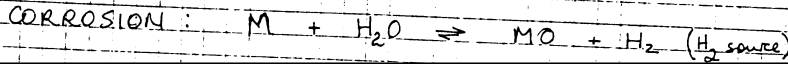
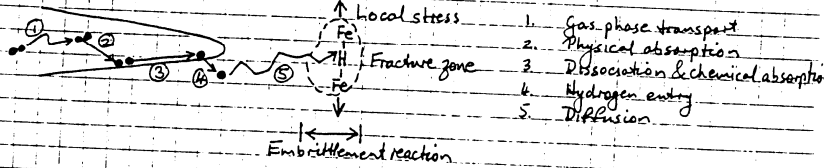
# Stress-Corrosion Cracking



CRITICAL THRESHOLD STRESS-INTENSITY FACTOR

FOR STRESS CORROSION CRACKING  $K_{SCC} \sim (0.1 \rightarrow 0.7) \times \text{YIELD STRESS}$

## HYDROGEN EMBRITTLEMENT



# STRESS-CORROSION CRACK GROWTH & FAILURE PREDICTION

For multiple mechanisms — regions I, II & III

Effective rate determined by slowest

$$\text{Writing } \frac{da}{dt} = \dot{a} \quad \frac{1}{\dot{a}_T} = \frac{1}{\dot{a}_I} + \frac{1}{\dot{a}_{II}} + \frac{1}{\dot{a}_{III}}$$

$$\approx \frac{1}{\dot{a}_I} + \frac{1}{\dot{a}_{II}}$$

$$\therefore \dot{a}_T = \frac{\dot{a}_I \dot{a}_{II}}{\dot{a}_I + \dot{a}_{II}}$$

& steady state cracking time  $t = \int_0^t dt = \int_{a_0}^{a_i} \frac{\dot{a}_I + \dot{a}_{II}}{\dot{a}_I \dot{a}_{II}} da$

where

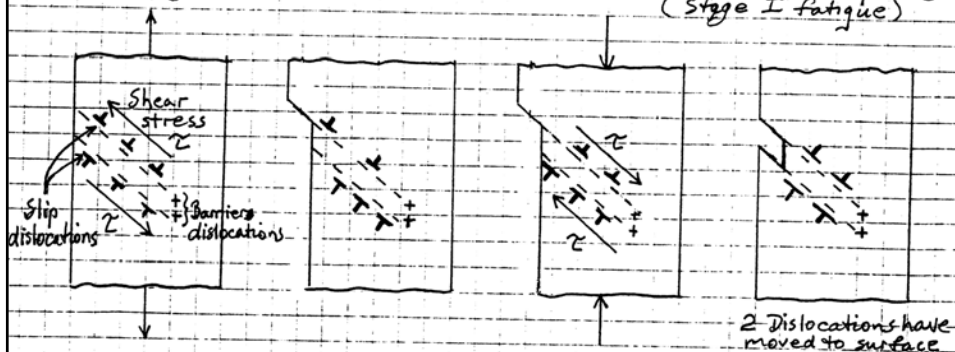
$$\dot{a}_I = C_1 e^{mk}$$

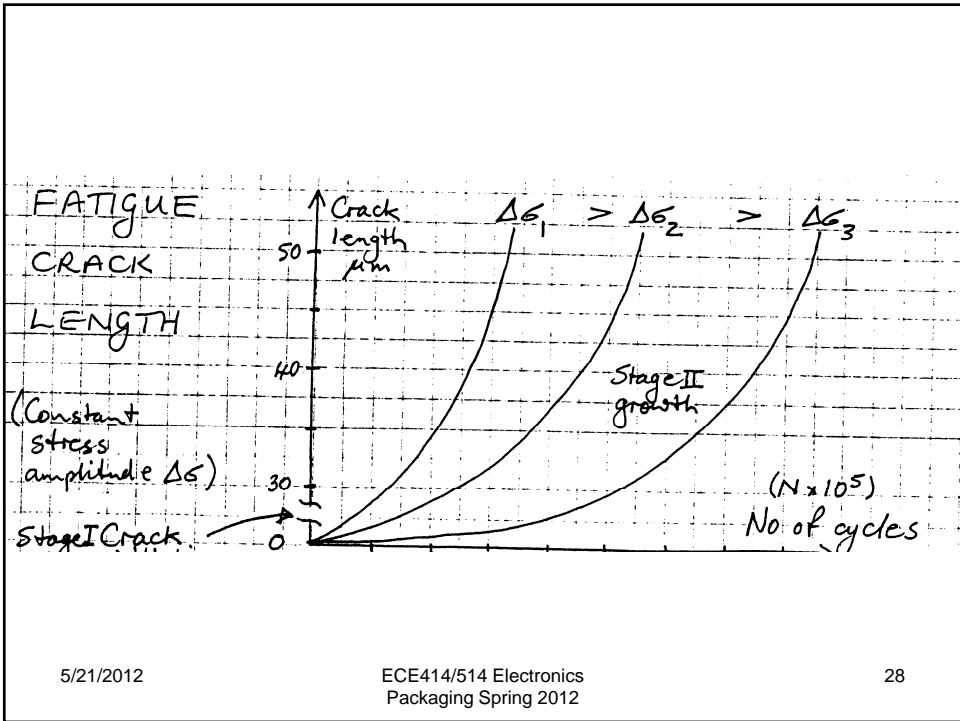
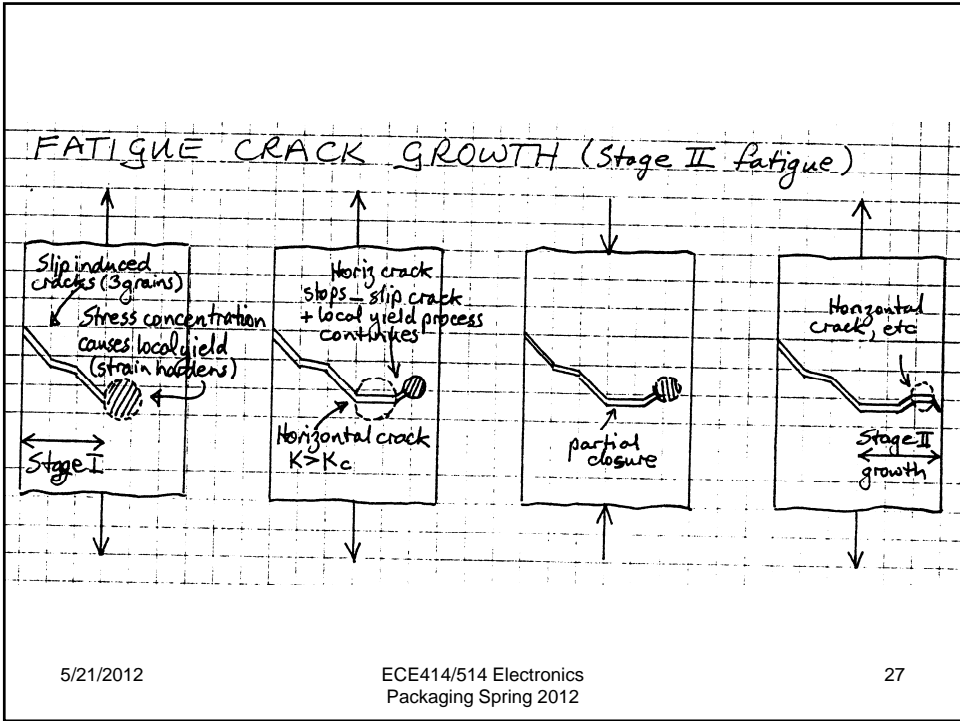
$$\dot{a}_{II} = C_2 P^n e^{-\Delta H/RT}$$

*C<sub>1, m</sub> functions of T, P*

## Fatigue Failure

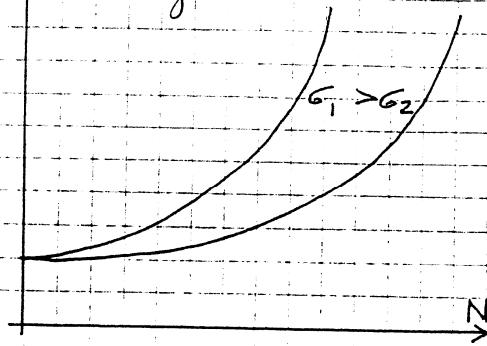
FATIGUE CRACK INITIATION (Cottrell-Hull simplified)  
(Stage I fatigue)





## Fatigue Life

$a$  ↑ Crack length



$$\frac{da}{dN} \propto \sigma^m a^n$$

$$m \approx 2-7$$

$$n \approx 1-2$$

Empirical relationship:  $\frac{da}{dN} = A \cdot \Delta K^m$

where  $\Delta K = Y \Delta \sigma \sqrt{a}$   
 ↑  
 geometrical correction

Failure lifetime  $N_f = \int dN = \int_{a_0}^{a_f} A^{-1} \Delta K^{-m} da$

where  $a_0$  = initial crack size,  $a_f$  = final crack size at failure

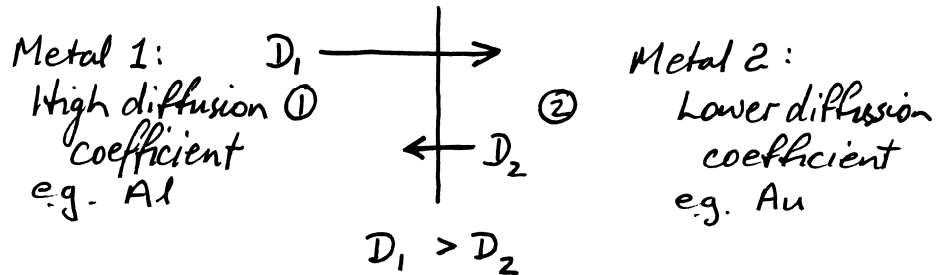
$$\begin{aligned} N_f &= \int_{a_0}^{a_f} A^{-1} Y^{-m} \Delta \sigma^{-m} a^{-m/2} da \\ &= \frac{1}{A Y^m \Delta \sigma^m} \left[ \frac{a^{-\frac{m}{2}+1}}{-\frac{m}{2}+1} \right]_{a_0}^{a_f} \\ &= \frac{2}{(m-2) A Y^m \Delta \sigma^m} \left\{ \frac{1}{a_0^{(m/2-1)}} - \frac{1}{a_f^{(m/2-1)}} \right\} \end{aligned}$$

$A, m$  material constants

for  $m \neq 2$

## Kirkendall Voids

Interface — dissimilar metals



Net effect:  
Voids develop on Metal 1 side

① Al | Au ②

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- \* High resistance interface
- \* Mechanically weakened
- \* Diffusion constants increase rapidly with temperature.  
∴ Must keep temperatures low  
(temperature × time)

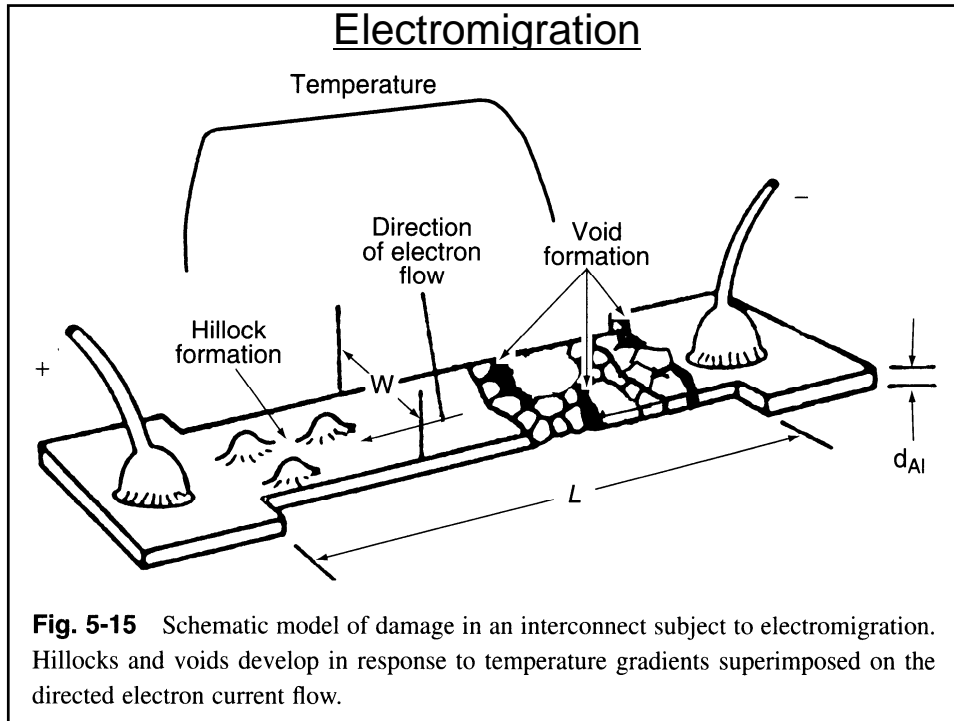
Also: Au/Cu → ductile intermetallics & voids  
→ decreased bond strength

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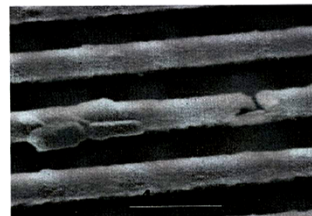




## Thermo- and Electrotransport Fail Mechanisms

### 3(a) Electromigration

- **Failure site:** Metallization traces.
- **Failure mode:** Increase in resistance leading to open circuit, short between lines.
- **Failure mechanism:** Transport of ions through a conductor resulting from a passage of direct current leading to formation of voids / hillocks.
- **Environmental/operating loads:** Temperature, current density.



## Electromigration

- **Damage model**

$$T_f (\text{hours}) = \frac{Z_{met} * t_{met}}{(j_{met})^{\epsilon_{met}} * C * \exp\left(\frac{-H_{gb}}{K * T_{die}}\right)}$$

- **Package attributes**

Metallization width, thickness.

- **Accelerated tests**

High temperature operating life with bias.

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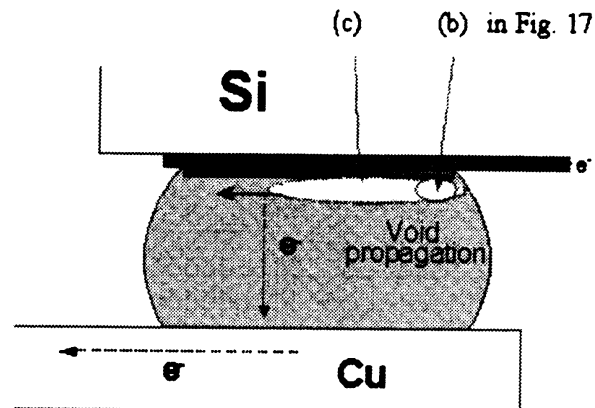
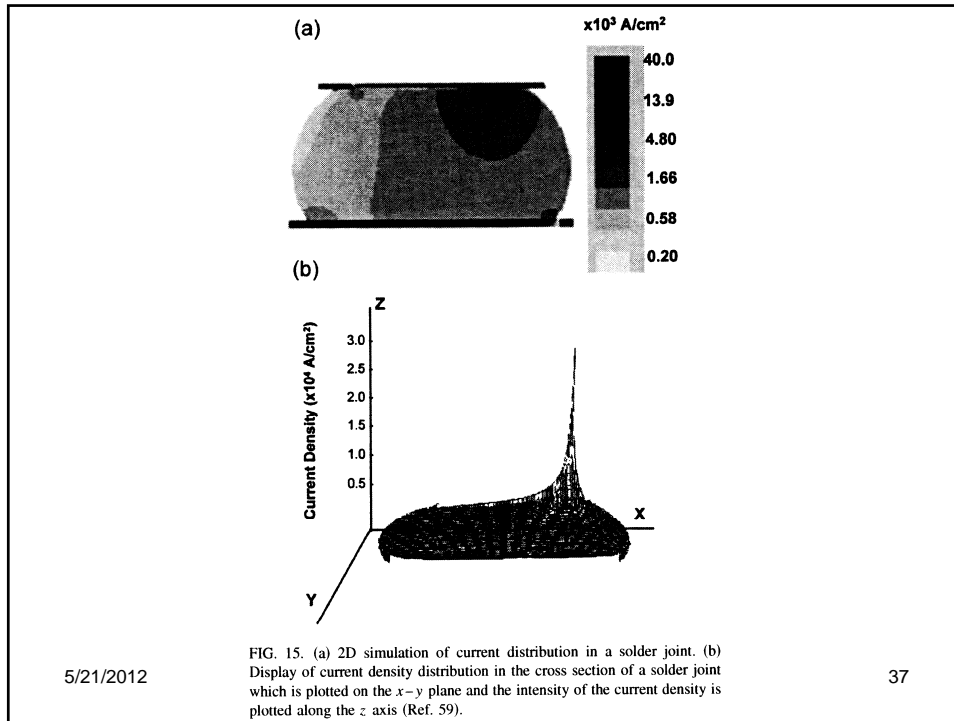


FIG. 19. Schematic diagram depicting the effect of void formation and propagation on the current entering the solder bump. While the current is being displaced to the front of the void, there is little change in resistance. Only when the void has propagated across the entire contact interface, the resistance will jump abruptly (Ref. 59).



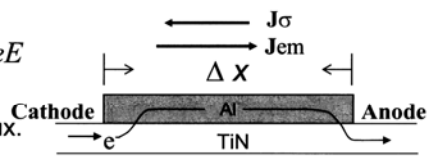
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## Critical Product in Short Strip

$$J = -C \frac{D}{kT} \frac{d\sigma\Omega}{dx} + C \frac{D}{kT} Z^* eE$$

If  $J=0$ , there is no net electromigration flux.



$$\Rightarrow \frac{\Delta\sigma\Omega}{\Delta x} = Z^* e\rho j \quad E = \text{Electric Field } (E = \rho j)$$

$$\Rightarrow \text{Critical product} \quad (j \Delta x)_{\text{critical}} = \frac{\Delta\sigma\Omega}{Z^* e\rho}$$

If  $j\Delta x < (j\Delta x)_c \Rightarrow$  No electromigration damage

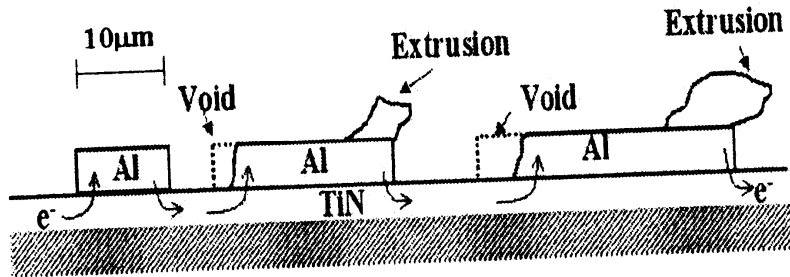


FIG. 6. Schematic diagram of a set of Al strips of different lengths patterned on a base line of TiN. The longer the length, the larger the depletion at the cathode. Below the critical length, there is no electromigration damage as depicted by the last one on the left-hand side.

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TABLE I. Melting point and diffusivities of Cu, Al, and eutectic SnPb.

	Melting point (K)	Temperature ratio 373 K/T m	Diffusivities at 100 °C (cm <sup>2</sup> /s)	Diffusivities at 350 °C (cm <sup>2</sup> /s)
Cu	1356	0.275	Lattice $D_l = 7 \times 10^{-28}$ Grain boundary $D_{gb} = 3 \times 10^{-15}$ Surface $D_s = 10^{-12}$	$D_l = 5 \times 10^{-17}$ $D_{gb} = 1.2 \times 10^{-9}$ $D_s = 10^{-8}$
Al	933	0.4	Lattice $D_l = 1.5 \times 10^{-19}$ Grain boundary $D_{gb} = 6 \times 10^{-11}$	$D_l = 10^{-11}$ $D_{gb} = 5 \times 10^{-7}$
Eutectic SnPb	456	0.82	Lattice $D_l = 2 \times 10^{-9} - 2 \times 10^{-10}$	Molten state $D_l > 10^{-5}$

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## Small Critical Product in Solders

$$(j\Delta x)_c = \frac{\Delta \sigma \Omega}{Z^* e \rho} \rightarrow (j\Delta x)_c = \frac{Y \Delta \epsilon \Omega}{Z^* e \rho} \quad \Delta \sigma = Y \Delta \epsilon, \Delta \epsilon = 0.2\% \text{ at elastic limit}$$

	Y(Gpa)	Z*	$\rho(\mu\Omega\text{-cm})$
<b>Solder</b>	~30	~30	~22
<b>Al</b>	~69	2~4	~2
<b>Cu</b>	~110		

$$(j\Delta x)_{c\_solder} = \frac{Y \Delta \epsilon \Omega}{Z^* e \rho} \approx 5 \times 10^{-3} (j\Delta x)_{c\_Cu/Al}$$

$\begin{matrix} \nearrow 0.5 \\ \searrow 10 \end{matrix}$

- At constant  $\Delta x$ , the current density needed to fail solder is **2~3 orders smaller** than that needed to fail Al or Cu
- If Al or Cu fails at  $10^5$  to  $10^6$  A/cm<sup>2</sup>, solder will fail at  $10^3$  or  $10^4$  A/cm<sup>2</sup>

Electronic Thin Film Lab Materials Science & Engineering, UCLA  
(with permission)

## Mean Time To Failure

$$MTTF = A j^{-n} \exp\left(\frac{Q}{kt}\right) \quad n = 1.8, Q = 0.8 \text{ eV}$$

(By Flip Chip Technologies)  
(hrs)

	1.5 A ( $1.9 \times 10^4$ A/cm <sup>2</sup> )		1.8 A ( $2.25 \times 10^4$ A/cm <sup>2</sup> )		2.2 A ( $2.75 \times 10^4$ A/cm <sup>2</sup> )	
	Expected	Actual	Expected	Actual	Expected	Actual
100 °C			380	97	265	63
125 °C	108	573*	79.6	43	55.5	3
140 °C	46	121	34	32	24	1

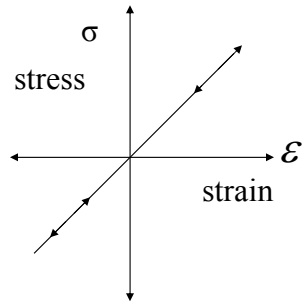
\* not failed,                      These MTTF are averaged value of three samples

**These results show that a small increase in j and T has dramatically reduced MTTF; a unique behavior of flip chip solder joint.**      by W.J. Choi, UCLA

Electronic Thin Film Lab Materials Science & Engineering, UCLA  
(with permission)

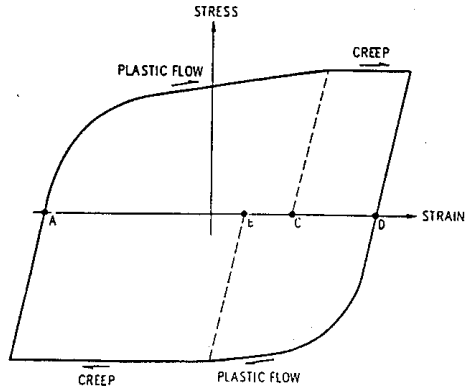
# Mechanical and Thermo mechanical Degradation mechanisms

- Mechanical



Ideal elastic material

## Elastic and plastic deformation

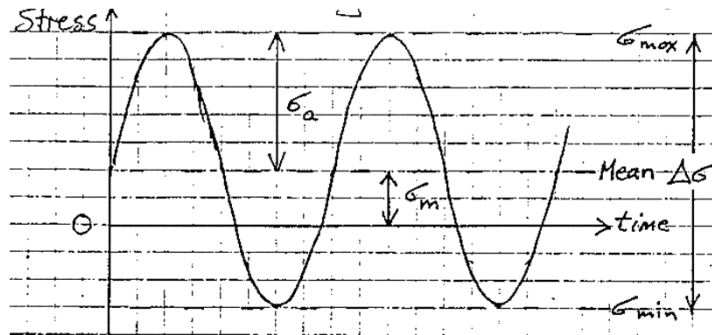


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## 1(a) Mechanical Fatigue Failure

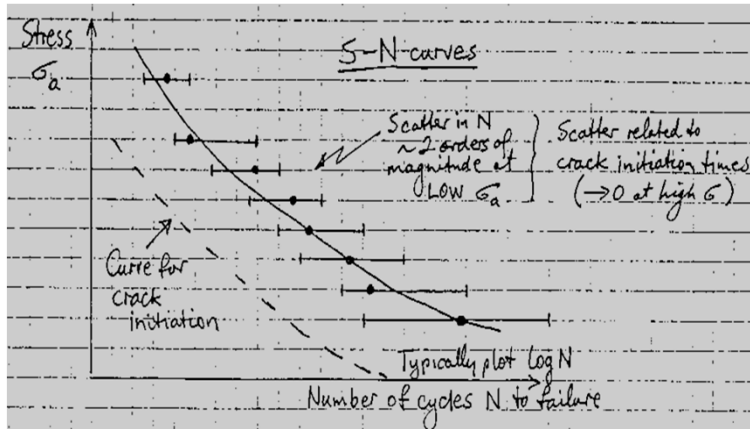


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## S-N curves

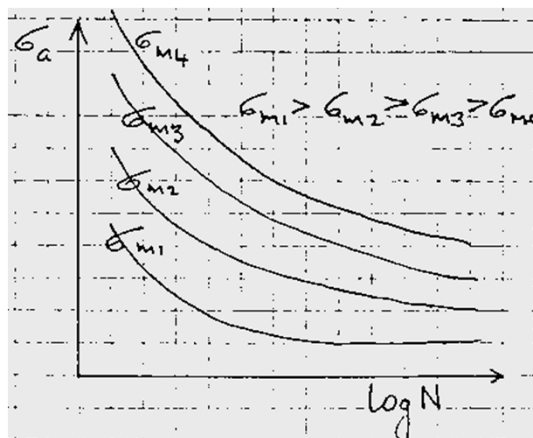


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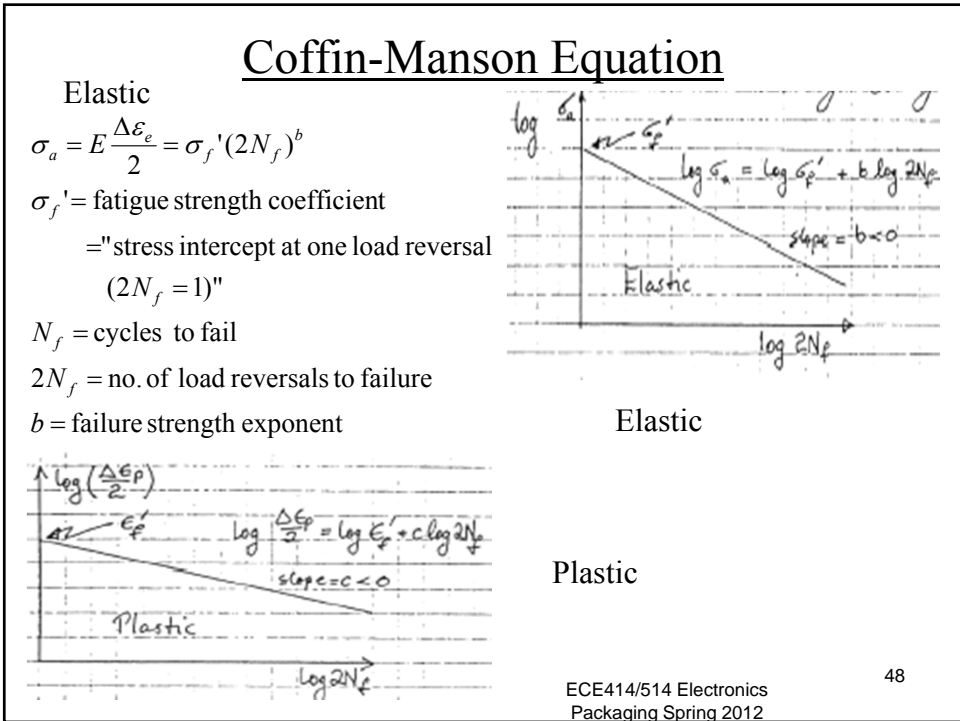
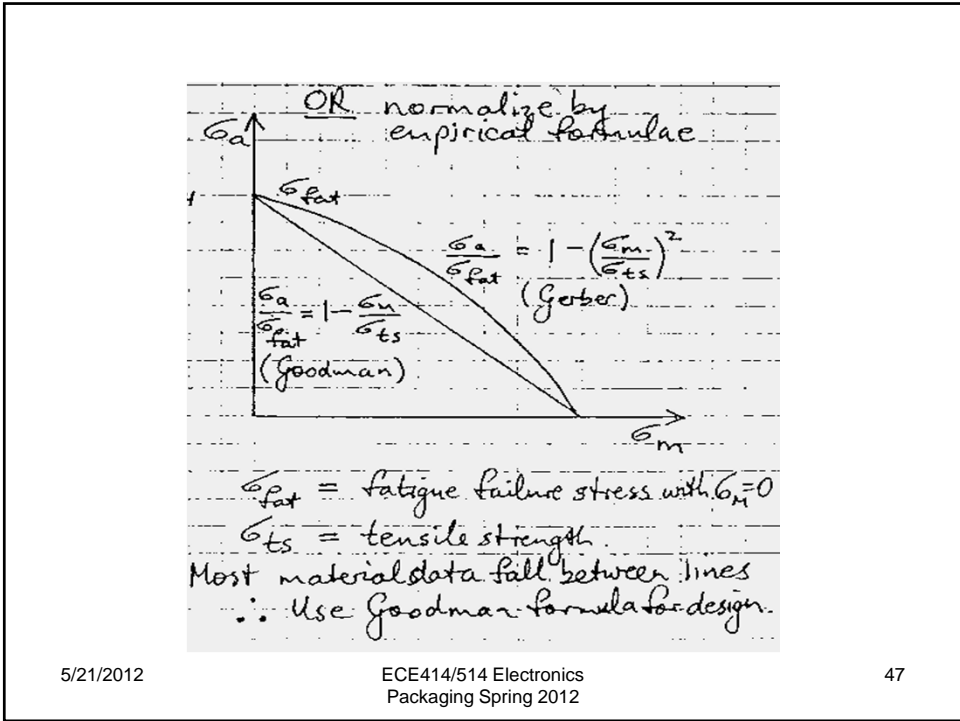
## Effect of mean stress $\sigma_m$



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$$\frac{\Delta \epsilon_p}{2} = \epsilon_f' (2N_f)^c$$

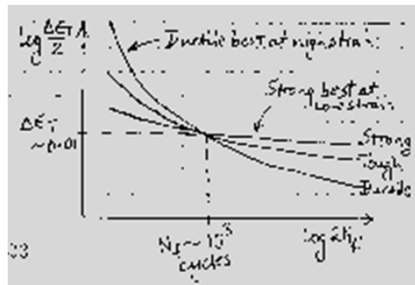
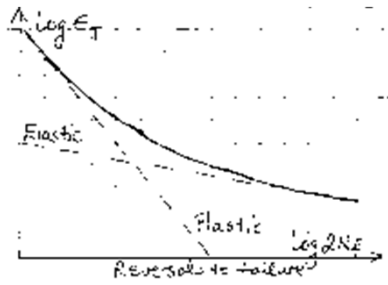
$\epsilon_f'$  = fatigue ductility coefficient

= "strain intercept at one load ( $2N_f = 1$ )"

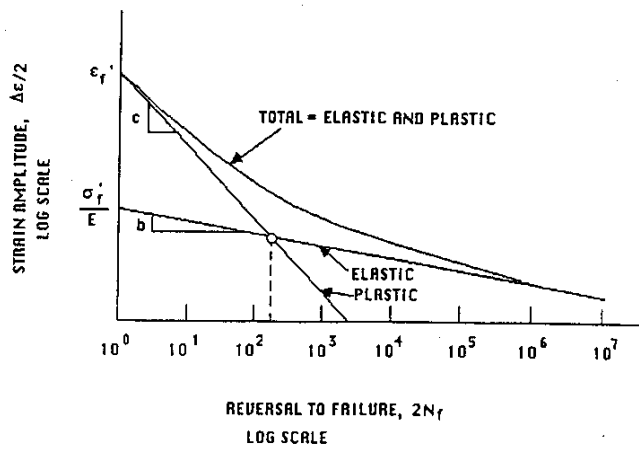
$c$  = fatigue ductility exponent ( $-0.5 < c < -0.7$ )

Total strain

$$\frac{\Delta \epsilon_T}{2} = \frac{\Delta \epsilon_e}{2} + \frac{\Delta \epsilon_p}{2} = \frac{\sigma_f'}{E} (2N_f)^b + \epsilon_f' (2N_f)^c$$



## Schematic representation of generalized Coffin-Manson relation



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## Palmer-Miner Cumulative Damage Law

- If number of cycle  $n_i$  at stress  $a_i$  which would cause failure  $N_i$  cycles, etc

Failure predicted at point where

$$\sum_{i=1}^k \frac{n_i}{N_i} = 1$$

where  $k$  = no. of different stress levels

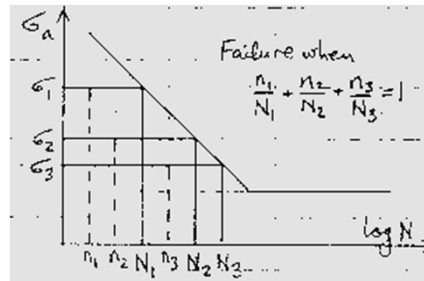
$\sigma_i$  =  $i$  th stress level

$n_i$  = no. of cycles at  $\sigma_i$

$N_i$  = fatigue life at  $\sigma_i$

Failure when

$$\frac{n_1}{N_1} + \frac{n_2}{N_2} + \frac{n_3}{N_3} = 1$$



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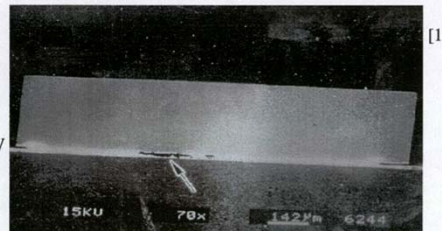
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## Fatigue

### Die Attach Fatigue

- **Failure Site:** Die attach
- **Failure Mode:** Delamination of die eliminating heat dissipation path and potentially causing thermal runaway and mechanical damage
- **Failure Mechanism:** Crack initiation during high plunger forces during die attach and high molding stresses and crack propagation due to CTE mismatch and temperature cycling
- **Environmental/Operating Loads:** Temperature cycling



[1]: FastAdvice 2.0, Sandia National Laboratory

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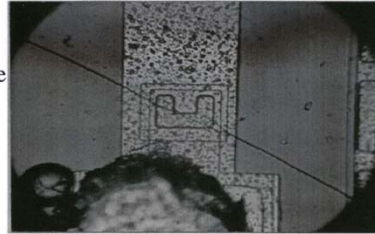
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# Fatigue

## Die Fracture and Die Fatigue

- **Failure site:** On chip/die
- **Failure mode:** Open circuit due to fracture
- **Failure mechanism:** Crack initiation during back grinding operation, high plunger forces during die attach and high molding stresses. Crack propagation due to CTE mismatch between the die and the substrate leading to catastrophic failure.
- **Environmental/operating loads:** Temperature, and temperature cycling



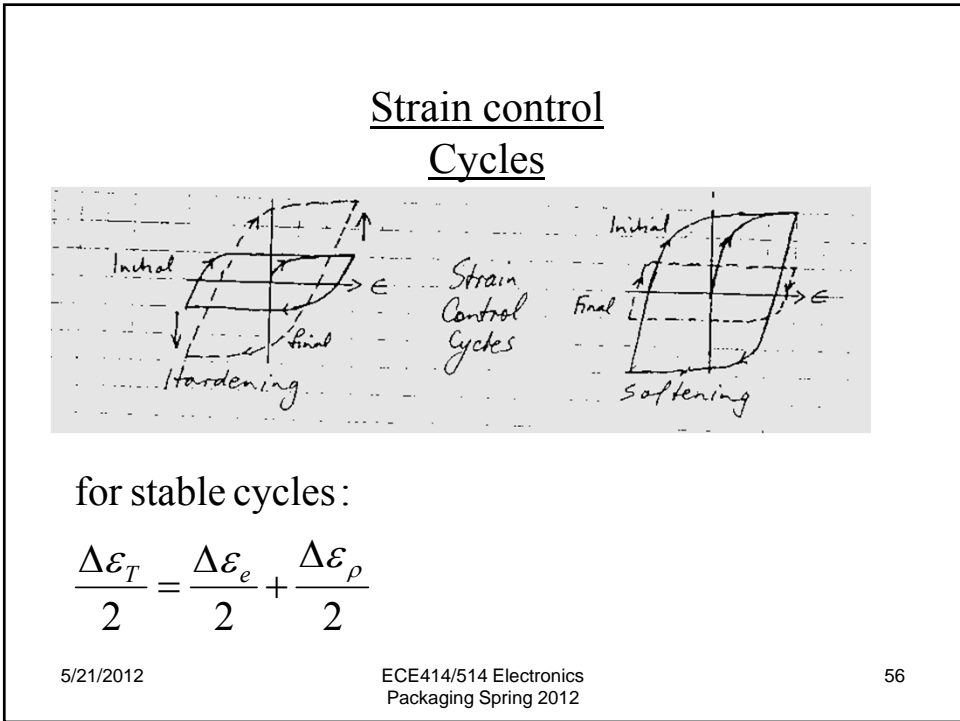
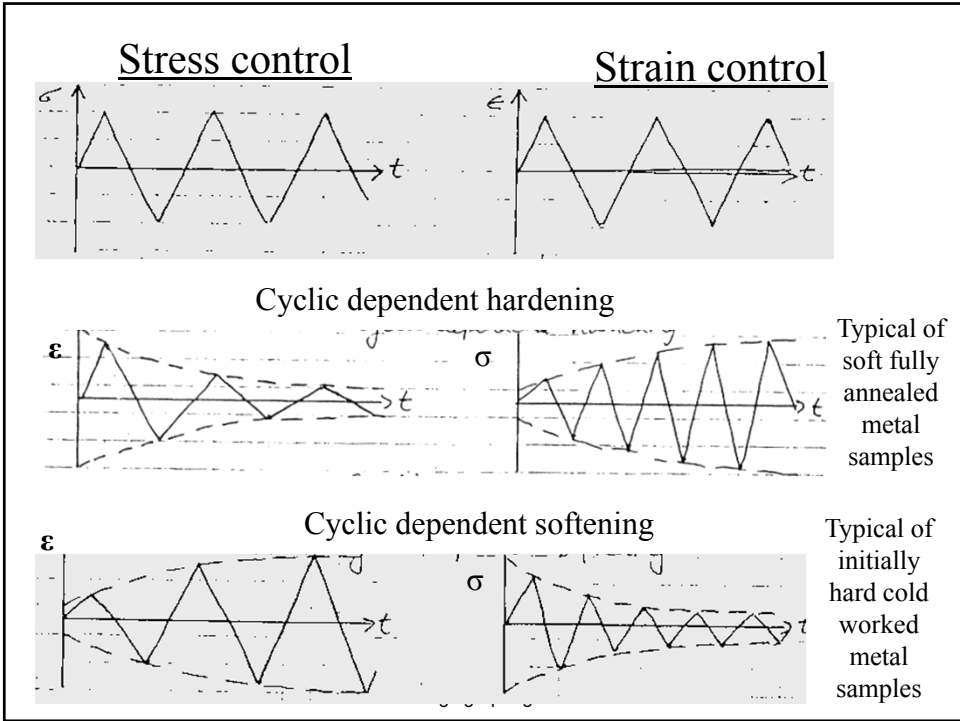
[1]:FastAdvice 2.0, Sandia National Laboratory

# Fatigue

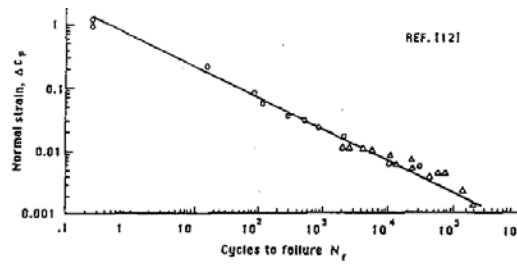
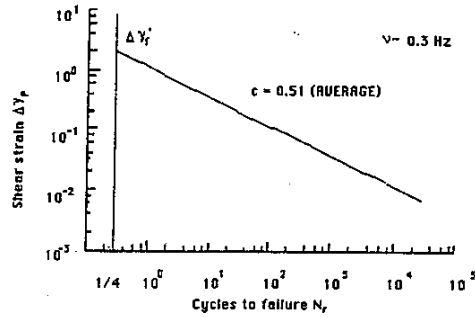
- *There are two ways in which materials can be fatigued:*
  - Mechanical cycle, by applying a sinusoidal stress of constant amplitude.
  - Thermal cycle generates a constant strain

Hence:

- Stress control for mechanical failure
- Strain control for thermomechanical failure (thermal cycling)



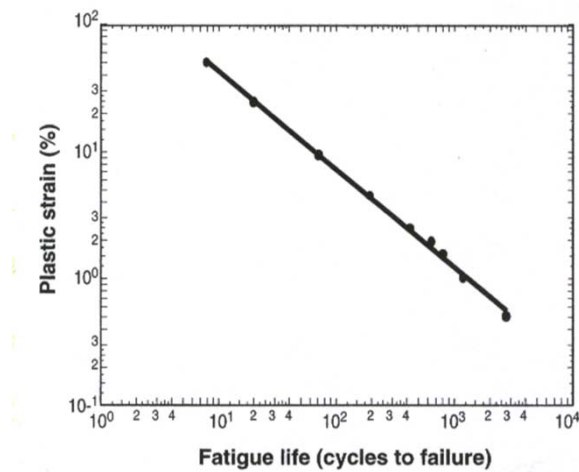
Plotting the log of the plastic strain amplitude versus the log of the cycles to failure → a st. line



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Effect of Plastic strain on fatigue life



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# Mechanical and Thermomechanical Degradation mechanisms

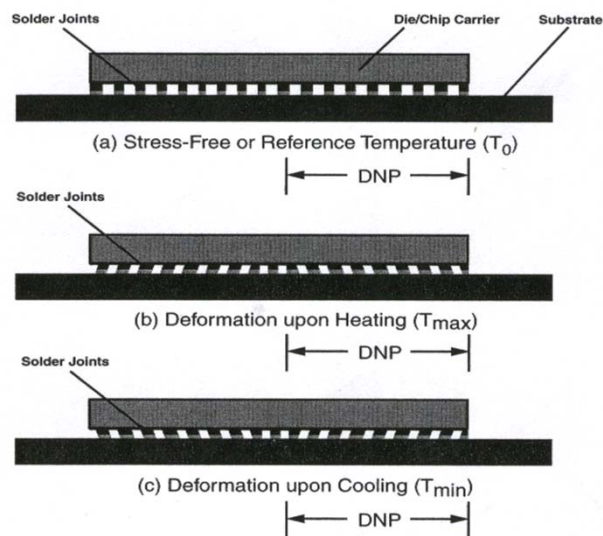
## Thermomechanical

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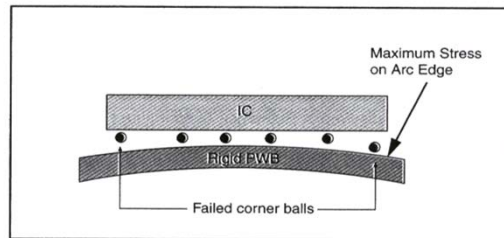
## Thermomechanical Deformation in solder joints



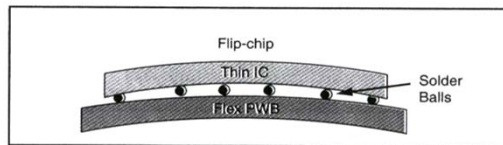
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## Maximum stress at the edge due to a large DNP (distance from neutral point)



a) Rigid



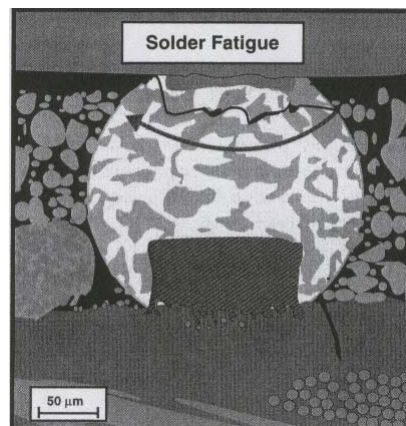
b) Thin or Compliant

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## Nucleation and propagation of fatigue crack in solder joints

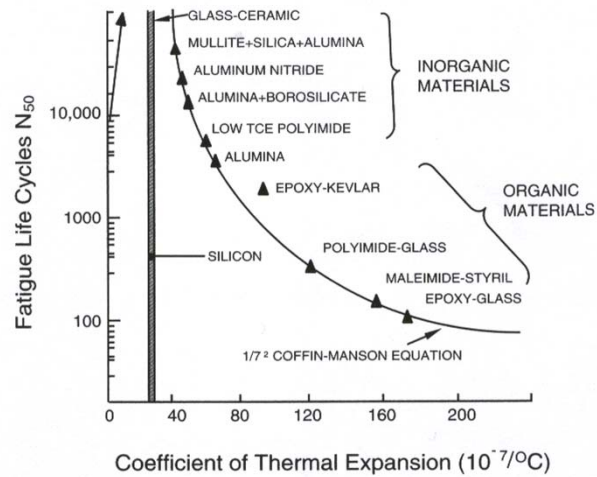


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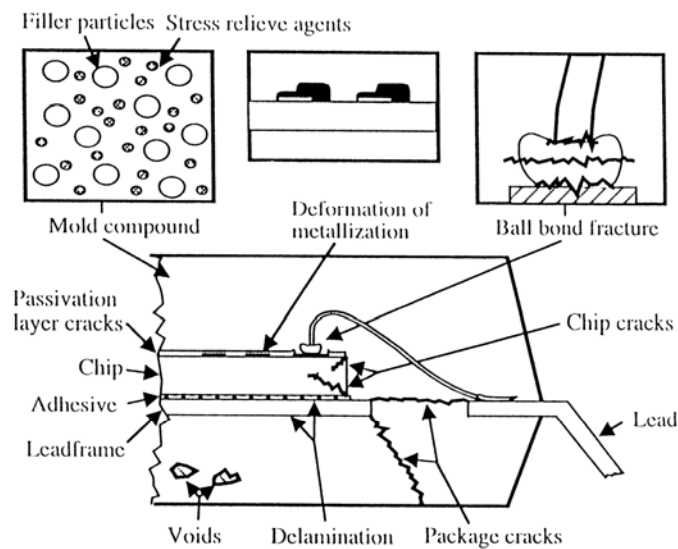
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## Fatigue life for MCM solder joints on the various substrate materials vs. material's CTE



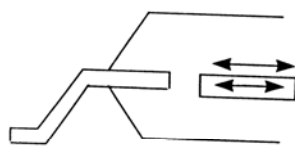
## Plastic Package Failure Mechanisms



**Figure 6.1** Typical failure mechanisms, sites, and modes in plastic-encapsulated devices

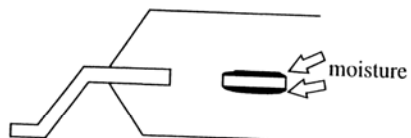


## Thermal & Humidity Modes



1

- thermomechanical stresses due to thermal expansion mismatches



2

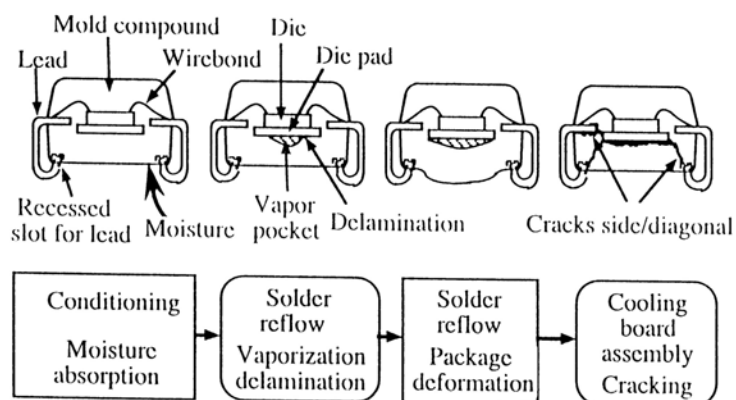
- ingress of moisture
- accumulation at interfaces
- rapid localized vaporization of moisture during IR reflow

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## Popcorn Failure



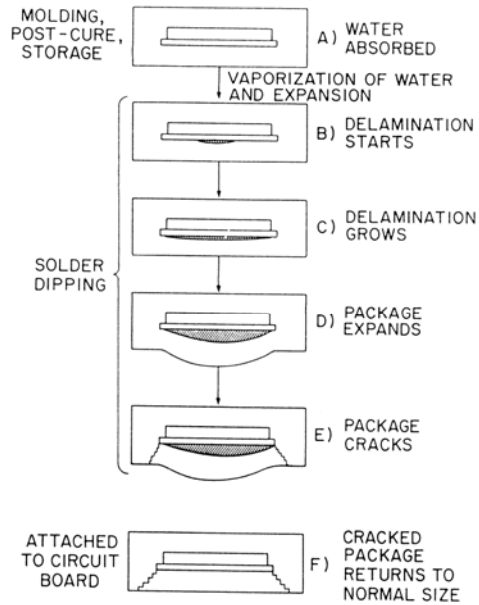
**Figure 4.12** Conditions leading to package popcorning during assembly [Nguyen 1993]

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# Popcorn Mechanism

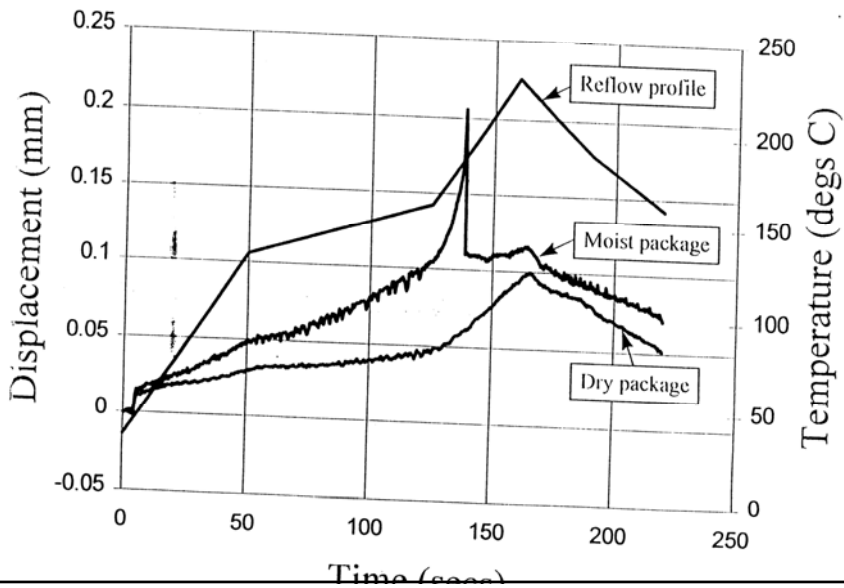


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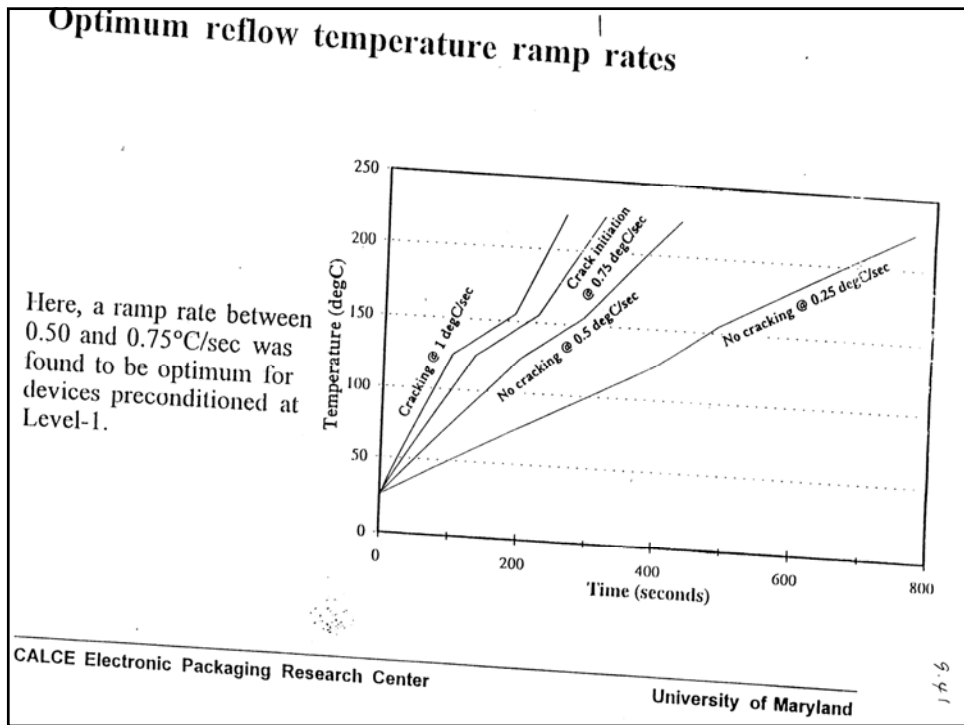
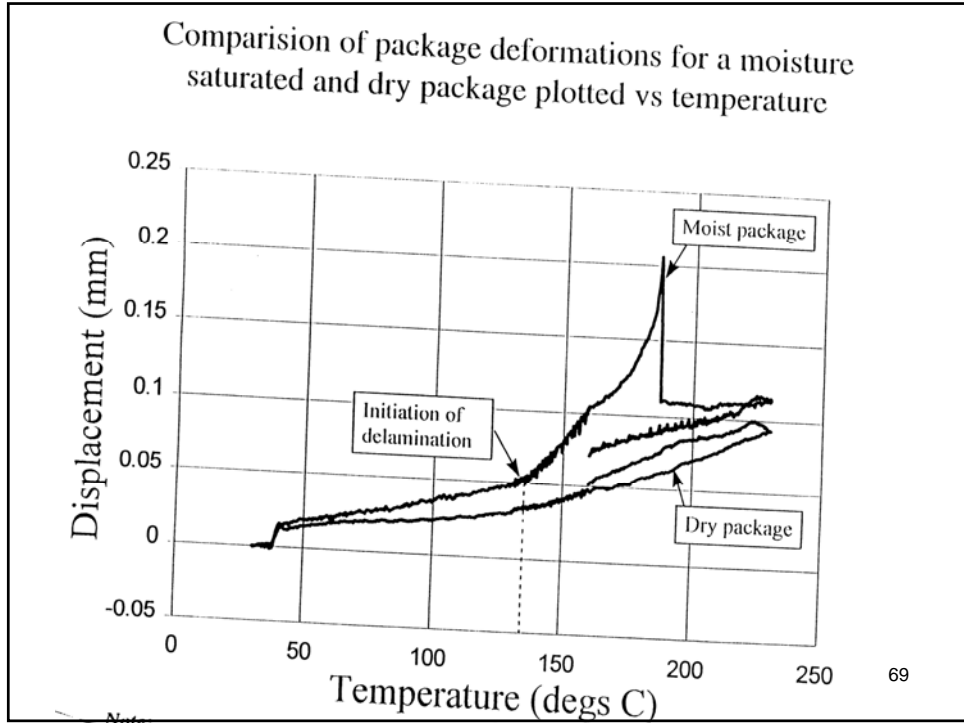
FIGURE 8-8 Mechanism for moisture-induced package cracking on surface moun

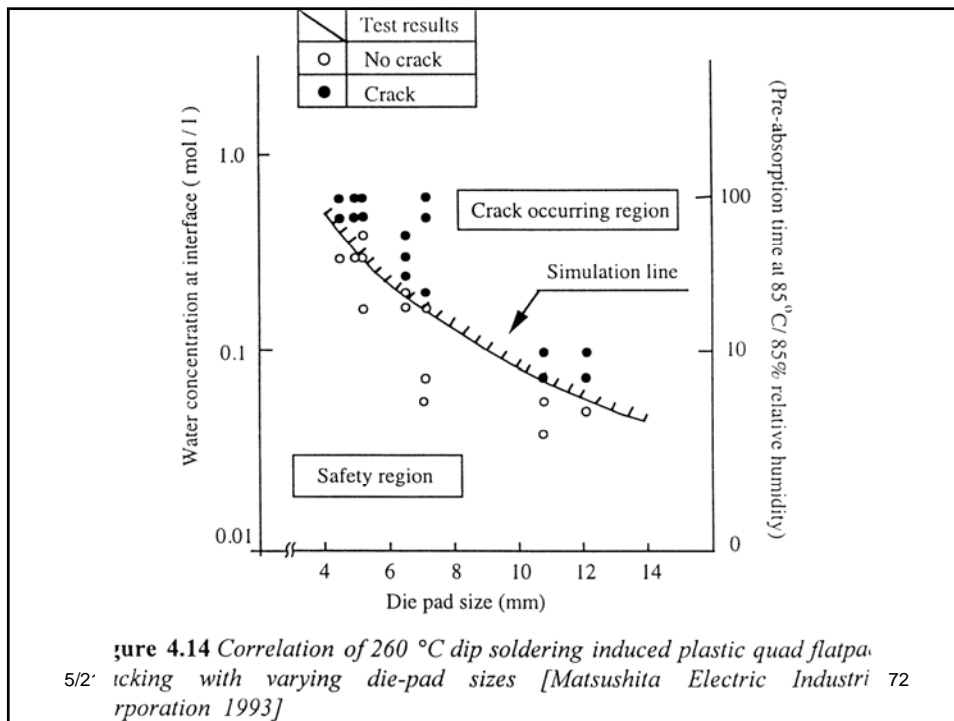
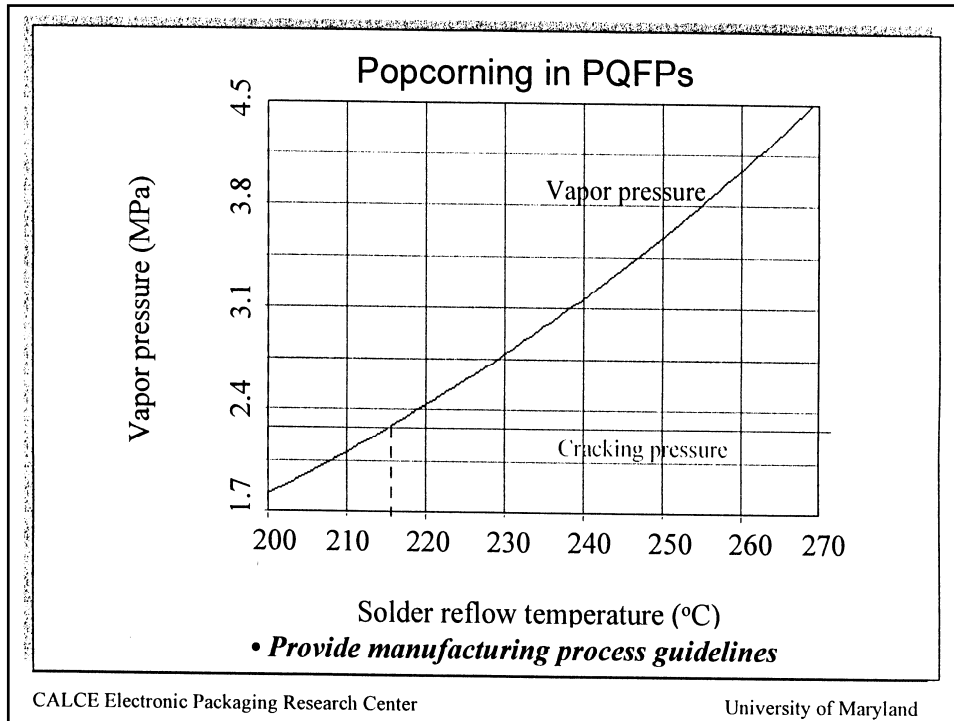
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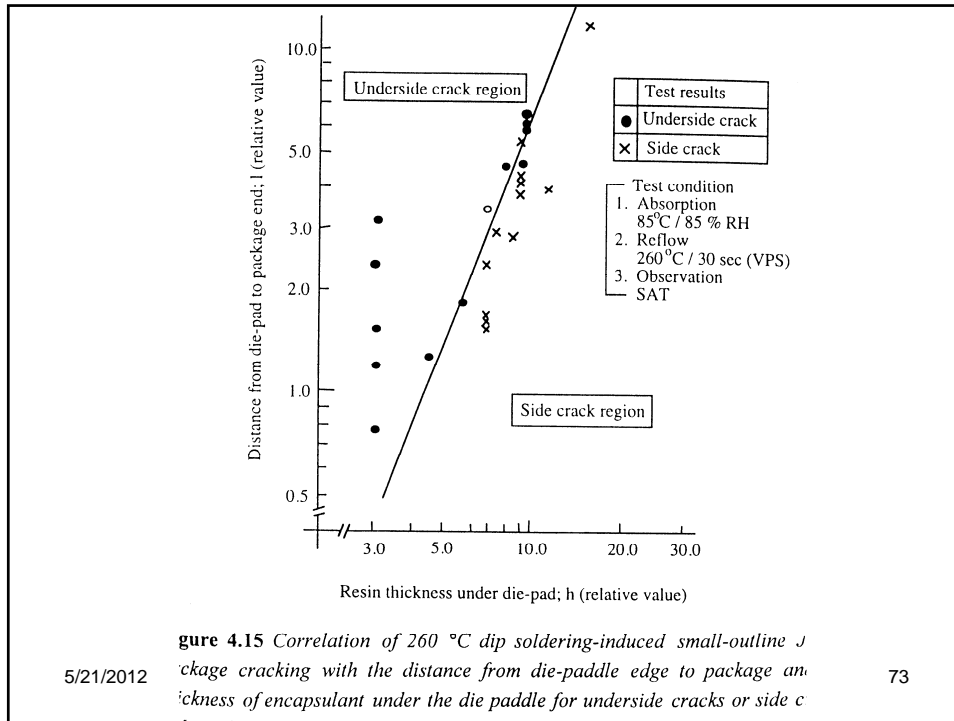
## Comparison of package deformations for a moisture saturated and dry package plotted vs time



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## Packing Materials

### Caution label

Affixed to the outside surface of the moisture barrier bag.

The label provides:

- Factory seal date
- Shelf life in bag
- Shelf life out of bag (classification level)
- Baking instructions

**Caution**  
This bag contains  
**MOISTURE-SENSITIVE DEVICES**

Level

1. Shelf life in sealed bag: 12 months at < 40°C and < 90% Relative humidity (RH).
2. After this bag is opened, devices that will be subjected to infrared reflow, vapor-phase reflow, or equivalent processing (peak package body temp. 220°C) must be:
  - a) Mounted within \_\_\_\_\_ hours/days at factory conditions of ≤ 30°C/60% RH, or
  - b) Stored at ≤ 20% RH.
3. Devices require baking, before mounting, if:
  - a) Humidity card is > 20% when read at 23°C ±5°C or
  - b) 2a or 2b are not met.
4. If baking is required, devices may be baked for:
  - a) 192 hours at 40°C +5°C/-0°C and < 5% RH for low-temperature device containers, or
  - b) 24 hours at 125°C ±5°C for high-temperature device containers.

Bag Seal Date: \_\_\_\_\_  
(If blank, see bar code label)

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